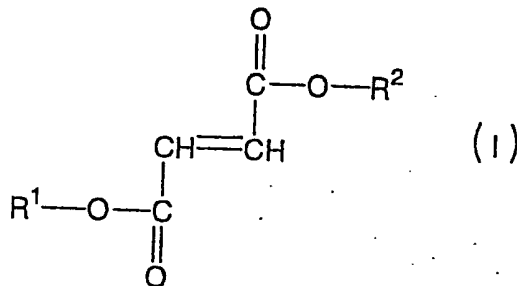


**IN THE CLAIMS:**

Cancel claims 1 and 4.

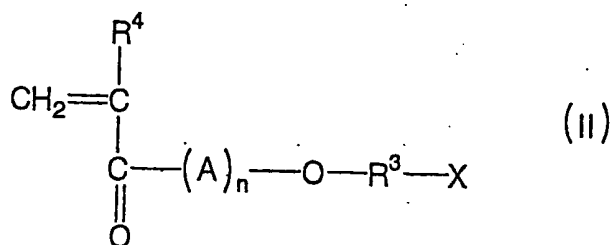
Amend claims 2, 3 and 5-9 as follows, the amendments being shown by brackets and underlining in an Appendix hereto:

2. (Amended) The polymer material as claimed in claim 3, wherein the fumaric diester is represented by the following formula (I):

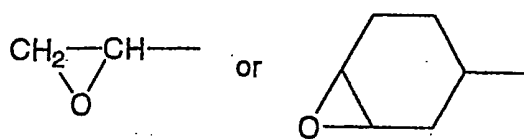


wherein R<sup>1</sup> represents an alkyl group or a cycloalkyl group; R<sup>2</sup> represents an alkyl group, a cycloalkyl group or an aryl group; and R<sup>1</sup> and R<sup>2</sup> may be the same or different.

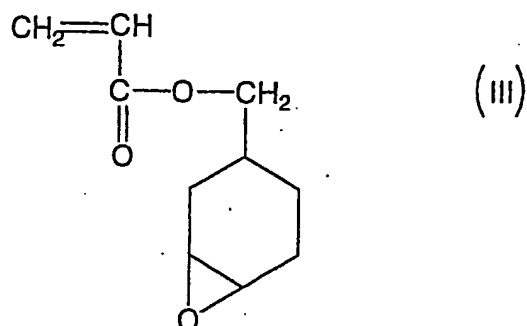
3. (Amended) A polymer material obtained through copolymerization of a monomer composition that contains, as monomers, a fumaric diester and an epoxy group-having (meth)acrylate represented by following formula (II):



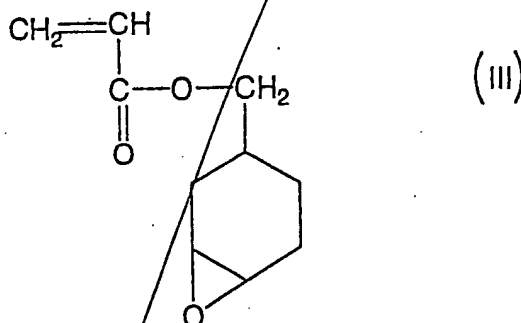
wherein  $\text{R}^3$  represents an alkylene group having from 1 to 4 carbon atoms;  $\text{R}^4$  represents H or  $\text{CH}_3$ ; A represents an alkylene oxide having from 2 to 4 carbon atoms; n indicates an integer of from 0 to 2; and X represents



5. (Amended) The polymer material as claimed in claim 3, wherein the epoxy group-having (meth)acrylate is represented by following formula (III):



6. (Amended) The polymer material of low relative permittivity as claimed in claim 2, wherein the epoxy group-having (meth)acrylate is represented by following formula (III):



7. (Amended) A film of the polymer material of claim 1.
8. (Amended) A substrate formed of the polymer material of claim 1.
9. (Amended) An electronic unit formed of the polymer material of claim 1.

### REMARKS

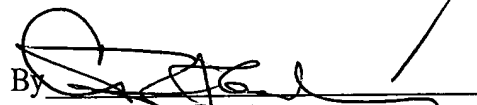
The term "low relative permittivity" has been deleted from the claims in view of the 35 U.S.C. 112, second paragraph rejection.

The broadest claim not rejected in the 35 U.S.C. 103(a) rejection was claim 3. That claim has now been amended to be in independent form and the remaining claims are directly or ultimately dependent from claim 3.

Therefore, it is apparent that no discussion of the 35 U.S.C. 103(a) rejection is necessary and that the application is now in condition for allowance.

Respectfully submitted,

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